

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE****In re United States Patent Application of:****Applicant: KORZENSKI, Michael B., et al.****Application No.: 10/807,858****Date Filed: March 24, 2004**

**Title: COMPOSITION USEFUL FOR  
REMOVAL OF BOTTOM  
ANTI-REFLECTION  
COATINGS FROM  
PATTERNED ION-  
IMPLANTED PHOTORESIST  
WAFERS**

**Docket No.: 020732-110.694****Examiner: AHMED, Shamim****Art Unit: 1765****Confirm. No.: 5492****Customer No.:****24239**

**RESPONSE TO THE JANUARY 30, 2007 ADVISORY ACTION; REQUEST FOR A  
ONE-MONTH EXTENSION UNDER 37 CFR §1.136(a); AND REQUEST FOR  
CONTINUED EXAMINATION IN UNITED STATES PATENT APPLICATION NO.  
10/807,858**

Mail Stop AF  
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

Sir:

This responds to the January 30, 2007 Advisory Action in the above-identified application.

The claims of the application are set out in the following **Section I (The Claims)**.

Remarks addressing the substance of the January 30, 2007 Advisory Action are set out in the **Section II (Remarks)** hereof.